

Title (en)

Method of forming a mask pattern on a substrate

Title (de)

Verfahren zur Herstellung eines Maskenmusters auf einem Substrat

Title (fr)

Procédé de fabrication d'un motif de masque sur un substrat

Publication

EP 1555863 A1 20050720 (EN)

Application

EP 05250159 A 20050114

Priority

GB 0400982 A 20040116

Abstract (en)

A method of forming a two-dimensional mask pattern on a substrate (1). The method comprises: (a) printing a non-electrically conductive material (2) on a substrate in a coarse version of a desired mask pattern; and (b) selectively ablating a portion of the material using a laser to refine the coarse pattern to form the desired mask pattern, thereby forming clearly defined and accurate gaps (4). <IMAGE> <IMAGE>

IPC 1-7

H05K 3/00; **H05K 3/06**; **H05K 3/28**

IPC 8 full level

G03F 1/08 (2006.01); **H05K 3/00** (2006.01); **H05K 3/28** (2006.01); **H05K 3/04** (2006.01); **H05K 3/06** (2006.01); **H05K 3/12** (2006.01)

CPC (source: EP US)

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Citation (applicant)

- US 4767489 A 19880830 - LINDNER FREDERICK H [US]
- US 4877644 A 19891031 - WU JEFF C [US], et al
- US 4985116 A 19910115 - METTLER JOHN H [US], et al
- US 5278385 A 19940111 - GEROME JACQUES [FR], et al
- US 2003184979 A1 20031002 - TSAI CHUNG-CHE [TW], et al
- US 5147680 A 19920915 - SLYSH PAUL [US]
- EP 1067436 A1 20010110 - TOKYO OHKA KOGYO CO LTD [JP]

Citation (search report)

- [XY] US 5147680 A 19920915 - SLYSH PAUL [US]
- [AY] US 4414059 A 19831108 - BLUM SAMUEL E [US], et al
- [DAY] US 4767489 A 19880830 - LINDNER FREDERICK H [US]
- [DAY] US 4877644 A 19891031 - WU JEFF C [US], et al
- [DAY] US 4985116 A 19910115 - METTLER JOHN H [US], et al
- [AY] US 4376815 A 19830315 - ODDI MICHAEL J [US], et al
- [DAY] US 5278385 A 19940111 - GEROME JACQUES [FR], et al
- [A] US 6627091 B1 20030930 - VAN PUymbroeck JOZEF [BE]
- [A] PATENT ABSTRACTS OF JAPAN vol. 017, no. 444 (E - 1415) 16 August 1993 (1993-08-16)

Cited by

FR2899366A1; EP1843282A1; EP4048037A1; US9993982B2

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